



YES-CV200RFS Plasma Strip/Descum System

Powerful Cleaning Removes Photoresist, Polyimide and BCB;
With Gentle Descum Function

Specifications

Hardware	
Clean Room Compatibility	Class 10
Wafer Temperature Range	Ambient to 250 °C; 4 min. maximum ramp time
Capacity	Single wafer/pieces for 50mm - 200mm; Dual wafer/pieces for two 100mm
N ₂ Flow Rate	1.7 SCFM
Process Gas Flow Rate	20-50 SCCM average
Process Gas Inputs	4 standard
Mass Flow Controllers	Optional, up to 4 for gas mixing
Interior Chamber Dimensions	25.4 cm (W) x 28.575 cm (D) x 4.978 cm (H) (10" x 11.25" x 1.96")
Hot Plate Process Area	49 in ² maximum (200mm wafer)
Overall System Dimensions	59.7 cm (W) x 109.3 cm, door open (D) x 113.4 cm (H) (23.5" x 43" x 44.6")
Chamber Material	6061-T6 aluminum
Compliance	SEMI S2, CE, S8
Software	
Tool Control	PLC control of valves, temperature set points, plasma generation power, auto operation, touch screen interface
Number of Recipes	12 with load/save/loop/link capability
Range of Exposure Time	0-1200 seconds (20 minutes)
Resolution of Timer Setting	1 second
Performance	
RF Plasma Power	40 kHz, 100 – 1000 W capacitive, downstream
Process Pressure Measurement	Convection type pressure sensor, 0.1 mTorr to 1000 Torr (pressure measurement sensitive to process gas composition)
Vent Gas Consumption	0 SCF idle, 1.0 SCF peak, .44 SCF average
Reactant Gas Consumption	0 SCF idle, 4.2 x 10 ⁻³ peak and average
Heat Emission	920 watts average
Power Consumption with Pump	420W idle, 2100W peak, 1210W average
Throughput	1 wafer per minute (up to 200mm diameter), typically 90 seconds per wafer
Strip Rate	Up to 7,000 Angstroms per minute
Electron Shift	< 10mV electron shift in a 200A gate oxide variable plasma intensity
Uniformity (in wafer)	<10%
Cooling	Process chamber cooled by forced air convection
Additional	
Power Requirements	200-250V, 20 amps, 50/60 Hz, 1 phase
Power Supply	Automatic frequency tuning
System Weight	147.42 kg (325 lbs)
Shipping Weight, Crated (approx.)	295 kg (650 lbs.)
Crate Dimensions	139.7 cm (W) x 88.9 cm (D) x 144.78 cm (H) (55" x 35" x 57")



Contact Us

When you're ready to run process tests, a demonstration can be arranged using your chemicals and samples. Call +46 8 319000 or visit us at www.bitase.se

©2011 Yield Engineering Systems. Yield Engineering Systems and the Yield Engineering Systems logo are trademarks of Yield Engineering Systems, Inc. All other brands, product names and logos are trademarks or service marks of their respective owners. All specifications subject to change without notice. Individual process results may vary.